

70/593857

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

EXPRESS MAIL NO. EV809338217US

Appl No.	: N/A	Confirmation No.	N/A
Applicant	: Nam Hun Kim		
Filed	: September 22, 2006		
Title	: PLASMA CHAMBER HAVING PLASMA SOURCE COIL AND METHOD FOR ETCHING THE WAFER USING THE SAME		
TC/A.U.	: N/A		
Examiner	: N/A		
Docket No.	: 58409/N305		
Customer No.	: 23363		

PRELIMINARY AMENDMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Post Office Box 7068
Pasadena, CA 91109-7068
September 22, 2006

Commissioner:

Prior to examination, please amend the above-identified application as follows:

Amendments to the Specification begin on page 2 of this paper.

Remarks/Arguments begin on page 3 of this paper.

Appendix an Abstract of the Disclosure, on a separate page, is attached following page 3 of this paper.